

6,153,504 Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2497		SERIAL NO. 10/776,553	
LIST OF REFERENCES BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.			
				FILING DATE February 10, 2004		GROUP 2811	

  

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
P	AA	6,153,504	11-2000	Shields et al.			
O	AB	4,971,655	11-1990	Stefano et al.			
	AC						
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FOREIGN PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
B	AM	08-045926A	02-1996	Japan (abstract)			
C	AN	10-163083	06-1998	Japan			x
	AO						
	AP						
	AQ						

  

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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	AS		
	AT		

  

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Sheet 1 of 12

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. <del>10/176,553</del>	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.		10/176,553	
				Priority FILING DATE August 17, 2000			
				GROUP Unknown			

  

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
G	AA	4,474,975	Clemons et al.				
0	AB	5,962,581	Hayase et al.				
	AC	5,677,015	Hasegawa				
	AD	5,783,493	Yeh et al.				
	AE	5,807,660	Lin et al.				
	AF	4,833,096	Huang et al.				
	AG	5,405,489	Kim et al.				
	AH	5,470,772	Woo				
	AI	5,652,187	Kim et al.				
	AJ	5,656,337	Park et al.				
	AK	4,805,683	Magdo et al.				
	AL	5,874,367	Dobson				
	AM	5,858,880	Dobson et al.				

  

FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AN <del>0-942,330</del>	<del>9/99</del>	<del>EPO</del>				
0	AO 9-50993	02/97	Japan				X
	AP <del>0-2341172</del>	<del>09/94</del>	<del>Japan</del>			X	
0	AQ 593,727	10/47	GB				

  

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0	AR	<del>withheld</del>	Weidman, R. et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", The Journal of Physical Chemistry, Vol. 92, No. 3, 1998,
			pp. 594-602.
0	AS		Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride
			Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.
0	AT		Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon
			Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.

  

EXAMINER <u>                    </u>	DATE CONSIDERED <u>4/5/05</u>
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 09/641,826	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
G	AA	5,219,613	6/93	Fabry et al.	—	—		
	AB	5,270,267	12/93	Ouellet	—	—		
	AC	5,541,445	7/96	Quellet	—	—		
	AD	6,022,404	02/00	Ettlinger et al.	—	—		
	AE	5,709,741	01/98	Akamatsu et al.	—	—		
	AF	4,648,904	03/87	DePasquale et al.	—	—		
	AG	4,158,717	06/79	Nelson	—	—		
	AH	5,667,015	09/97	Harestad et al.	—	—		
	AI	5,661,093	8/97	Ravi et al.	—	—		
	AJ	5,536,857	7/96	Narula et al.	—	—		
	AK	4,695,859	9/87	Guha et al.	—	—		
	AL	5,061,509	10/91	Naito et al.	—	—		
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
G	AM	5-263255	10/93	Japan	—	—	Yes	No
	AN	<del>0-464515 A3</del>	<del>01/92</del>	<del>EPO</del>	—	—		X
Q	AO	<del>0-771886 A1</del>	<del>05/97</del>	<del>EPO</del>	—	—		
	AP	63-157443	06/88	JP	—	—	X	
	AQ	<del>0-471185 A3</del>	<del>02/92</del>	<del>EPO</del>	—	—		
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Q	AR		Joubert, O. et al., "Application of Plasma Polymerized Methylsilane in an All Dry Resist Process for 193 and 248nm Lithography".					
			Microelectronic Engineering 30 (1996), pp. 275-278.					
Q	AS		Joshi, A. et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV					
			Photolithography", SPIE Vol. 1925 (1993), pp. 709-720.					
Q	AT		Matsuura, M. et al., "A Highly Reliable Self-Planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects. IEEE					
			IEDM Tech. Dig., 1997, pp. 785-788.					
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.			
				Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
C	AA	4,600,671	7/86	Saitoh et al.	—		
	AB	5,753,320	5/98	Mikoshiba et al.	—		
	AC	5,356,515	10/94	Tahara et al.	—		
	AD	5,731,242	3/98	Parat et al.	—		
	AE	6,054,379	4/00	Yau et al.	—		
	AF	5,948,482	9/99	Brinker et al.	—		
	AG	5,800,877	9/98	Maeda et al.	—		
	AH	5,260,600	11/93	Harada	—		
	AI	4,992,306	2/91	Hochberg et al.	—		
	AJ	4,702,936	10/87	Maeda et al.	—		
	AK	4,863,755	9/89	Hess et al.	—		
	AL	5,234,869	8/93	Mikata et al.			
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	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM 0 388807 A2/3	03/94	EPO	—			
	9-065851	02/97	JP	—			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
O	AN	Horie, O. et al., "Kinetics and Mechanism of the Reactions of O( <sup>3</sup> P) with SiH <sub>4</sub> , CH <sub>3</sub> SiH <sub>3</sub> , (CH <sub>3</sub> ) <sub>2</sub> SiH <sub>2</sub> , and (CH <sub>3</sub> ) <sub>3</sub> SiH", J. Phys. Chem. 1991, Vol. 95, pp. 4393-4400.					
Q	AO	McClatchie, S. et al., "Low Dielectric Constant Flowfill" Technology for IMD Applications", Proceed. of 3d Internatl. Dielectrics for ULSI Multilevel Interconnection Conf, Santa Clara, CA, Feb. 1997, pp. 34-40.					
	AP	Beekman, K. et al. "Sub-Micron Gap Fill and In-Situ Planarisation Using Flowfill" Technology", ULSI Conf, Portland, OR, Oct. 1996, pp. 1-7.					
	AQ	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-2.					
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[Signature]				4/15/05			
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. 097047,820	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
G	AA	5,302,366	4/94	Schuette et al.				
	AB	5,591,494	1/97	Sato et al.				
	AC	5,968,611	10/99	Kaloyeros et al.				
	AD	6,159,871	12/00	Loboda et al.				
	AE	5,461,003	10/95	Havemann et al.				
	AF	6,124,641	9/00	Matsuura				
	AG	5,554,567	9/96	Wang				
	AH	6,028,015	2/00	Wang et al.				
	AI	5,744,399	4/98	Rostoker				
	AJ	5,883,014	3/99	Chen				
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AK 0.728496-A2	03/96	EPO					
	AL 06.067019A	03/94	JP (abstract)					
	AM H72845-A3	01-2002	EPO					
	AN 08.213386A	08-1996	Japan					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
G	AO	IBM Technical Disclosure Bulletin, "Low-Temperature Deposition of SiO <sub>2</sub> , Si <sub>3</sub> N <sub>4</sub> , or SiO <sub>2</sub> -Si <sub>3</sub> N <sub>4</sub> ", Vol. 28, Iss. 9, p. 4170 (Feb. 1986).						
	AP	TEXT: Ruffa, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 313-313.						
Q	AO	ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes".						
		Electrochemical Society Meeting Abstract No. 358, 191 <sup>st</sup> Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.						
Q	AR	Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from						
		www.semiconductor-intl.com).						
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. <del>09/641826</del>	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.			
				Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,017,779	1/00	Miyasaka			
S	AB	6,156,674	12/00	Li et al.			
	AC	6,140,151	10/00	Akram			
	AD	5,314,724	5/94	Tsukune et al.			
	AE	5,376,591	12/94	Maeda et al.			
	AF	5,817,549	10/98	Yamazaki et al.			
	AG	6,072,227	6/00	Yau et al.			
	AH	6,001,741	12/99	Alers			
	AI	5,786,039	7/98	Brouquet			
	AJ	6,235,568 B1	5/01	Murthy et al.			
	AK	6,187,694 B1	2/01	Cheng et al.			
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes      No
	AL	2000060261A	03-2000	Japan			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.				
	AN		Grant, J., "Hatch's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 21.				
O	AO		Wolf, S. et al., "Silicon Processing for the VLSI Era", Vol. 1, pp. 437-441.				
	AP		McKenzie, D.R. et al., "New Technology for PACVD", Surface and Coatings Technology, Vol. 62, pp. 326-333 (1996).				
	AO		Shibata, N., "Plasma-Chemical Vapor Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Jap. Jour. of App. Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.				
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2497		Priority SERIAL NO. <del>00644-026</del>	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.			
				Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
9	AA	5,750,442	5/98	Juengling			
	AB	6,114,255	9/00	Juengling			
	AC	6,238,976 B1	5/01	Noble et al.			
	AD	6,008,121	12/99	Yang et al.			
	AE	5,140,390	8/92	Li et al.			
	AF	5,286,661	2/94	de Fresart et al.			
	AG	6,184,151 B1	2/01	Adair et al.			
	AH	6,225,217 B1	5/01	Usami et al.			
	AI	6,004,850	12/99	Lucas et al.			
	AJ	6,140,677	10/00	Gardner et al.			
	AK	6,133,096	10/00	Su et al.			
AL	6,136,636	10/00	Wu				
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM	868887A	09-1999	TW			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AN	Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography" Solid State Technology (March 1997), pp. 109-114.					
	AO	Dammel, R. B., et al., "Dependence of Optical Constants of AZ BARL™ Bottom Coating on Bake Conditions, SPIE Vol. 3049 (1997), pp. 963-973.					
	AP	TEXT: Heavens, O.S., "Optical Properties of Thin Solid Films", pp. 48-49.					
	AQ	TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10.					
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
					Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,933,721	8/99	Hause et al.	—	—		
	AB	5,981,368	11/99	Gardner et al.	—	—		
	AC	6,159,804	12/00	Gardner et al.	—	—		
	AD	6,130,168	10/00	Chu et al.	—	—		
	AE	6,235,591 B1	5/01	Balasubramanian et al.	—	—		
	AF	6,198,144 B1	3/01	Pan et al.	—	—		
	AG	5,801,399	9/98	Hattori et al.	—	—		
	AH	5,994,730	11/99	Shrivastava et al.	—	—		
	AI	6,040,619	3/00	Wang et al.	—	—		
	AJ	6,060,765	5/00	Maeda	—	—		
	AK	6,060,766	5/00	Mehta et al.	—	—		
	AL	6,451,504	09/02	Rolfson et al.	—	—		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM	<del>429473A</del>	<del>04-2001</del>	<del>TW</del>	—	—		
	AN	<del>429844A</del>	<del>02-2001</del>	<del>TW</del>	—	—		
C	AO	8046186	02-1996	Japan	—	—	X	
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AP	Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).						
	AQ	Wolf, "Silicon Processing for the VLSI Era, Vol. 2: Process Integration," © 1990, pp. 189-190.						
	AR							
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a	AA	6,133,613	10/00	Yao et al.			
	AB	6,087,267	07/00	Dockrey et al.			
	AC	5,543,654	08/96	Dennen			
	AD	5,656,330	08/97	Niiyama et al.			
	AE	5,872,035	02/99	Kim et al.			
	AF	4,444,617	04/84	Whitcomb			
	AG	6,071,799	06/00	Park et al.			
	AH	5,691,212	11/97	Tsai et al.			
	AI	6,187,657 B1	02/01	Xiang et al.			
	AJ	5,792,689	08/98	Yang et al.			
	AK	6,281,100 B1	08/01	Yin et al.			
	AL	6,323,101 B1	11/01	Li et al.			
	AM	5,413,963	05-1995	Yen et al.			
	AN	6,143,670	11-2000	Cheng et al.			
	AO	6,403,464	06-2002	Chang			
	AP	4,940,509	07-1990	Tso et al.			
AQ	5,429,987	04-1995	Allen				
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
Q	AR	8046188	02-1996	Japan			
	AS	7201716	08-1995	Japan			X
	AT	6232113	08-1994	Japan			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
AU							
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U.S. PATENT DOCUMENTS							
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d	AA	4,954,867	09/90	Hosaka			
	AB	5,441,797	08/95	Hogan et al.			
	AC	5,472,827	12/95	Ogawa et al.			
	AD	5,674,356	10/97	Nagayama			
	AE	5,710,067	01/98	Footo et al.			
	AF	5,741,721	04/98	Stevens			
	AG	5,759,755	06/98	Park et al.			
	AH	5,838,052	11/98	McTeer			
	AI	5,472,829	12/95	Ogawa			
	AJ	5,591,566	01/97	Ogawa			
	AK	4,910,160	03-1990	Jennings et al.			
	AL	6,200,835 B1	03-2001	Manning			
	AM	5,244,537	09-1993	Ohnstein			
	AN	6,204,168 B1	03-2001	Naik et al.			
	AO	4,562,091	12-1985	Sachdev et al.			
	AP	4,764,247	08-1988	Leveriza et al.			
AQ	5,986,318	11-1999	Kim et al.				
AR	6,087,064	07-2000	Lin et al.				

  

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AS							

  

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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AA	5,677,111	10/97	Ogawa					
AB	5,670,297	09/97	Ogawa et al.					
AC	5,698,352	12/97	Ogawa et al.					
AD	5,831,321	11/98	Nagayama					
AE	5,034,348	07/91	Hartswick et al.					
AF	5,340,621	8/23/94	Matsumoto et al.					
AG	5,600,165	2/4/97	Tsukamoto et al.					
AH	6,008,124	12/99	Sekiguchi et al.					
AI	5,968,324	10/99	Cheung et al.					
AJ	5,872,385	02/99	Taft et al.					
AK	5,883,011	04/99	Lin et al.					
AL	5,960,289	09/99	Tsui et al.					
AM	4,755,478	07-1988	Abernathy et al.					
AN	4,870,470	09-1989	Bass et al.					
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	AS							
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EXAMINER				DATE CONSIDERED				
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li et al.			
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2497		Priority SERIAL NO. 09/641,826	
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FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR						
	AS						
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